

ABSTRACT OF THE DISCLOSURE

A thin-film structure processing device for processing a thin-film structure formed on a substrate comprising a liquefied high-pressure inert gas storage section storing the liquefied high-pressure inert gas, and a
5 nozzle section for discharging liquefied inert gas stored by said liquefied high-pressure inert gas storage section into atmosphere pressure jetting jet flow including dry ice particles of inert gas to said thin-film structure, and wherein said nozzle section having the nozzle structure capable of forming the jet flow strong enough for grinding the thin-film composing said
10 thin-film structure by jetting the jet flow of said inert gas to the thin-film structure.